Stefan Slesazeck

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The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

108 papers

3,906 citations

33 h-index 60 g-index

117 ext. papers

5,158 ext. citations

5.7 avg, IF

6.05 L-index

#	Paper	IF	Citations
108	Physical Mechanisms behind the Field-Cycling Behavior of HfO2-Based Ferroelectric Capacitors. <i>Advanced Functional Materials</i> , 2016 , 26, 4601-4612	15.6	397
107	Reconfigurable silicon nanowire transistors. <i>Nano Letters</i> , 2012 , 12, 119-24	11.5	242
106	Unveiling the double-well energy landscape in a ferroelectric layer. <i>Nature</i> , 2019 , 565, 464-467	50.4	190
105	Switching Kinetics in Nanoscale Hafnium Oxide Based Ferroelectric Field-Effect Transistors. <i>ACS Applied Materials & District Applied & District</i>	9.5	179
104	Direct Observation of Negative Capacitance in Polycrystalline Ferroelectric HfO2. <i>Advanced Functional Materials</i> , 2016 , 26, 8643-8649	15.6	168
103	A 28nm HKMG super low power embedded NVM technology based on ferroelectric FETs 2016 ,		129
102	Novel ferroelectric FET based synapse for neuromorphic systems 2017,		121
101	A FeFET based super-low-power ultra-fast embedded NVM technology for 22nm FDSOI and beyond 2017 ,		121
100	Mimicking biological neurons with a nanoscale ferroelectric transistor. <i>Nanoscale</i> , 2018 , 10, 21755-217	63 7.7	117
99	The Past, the Present, and the Future of Ferroelectric Memories. <i>IEEE Transactions on Electron Devices</i> , 2020 , 67, 1434-1443	2.9	109
98	Nanoscale resistive switching memory devices: a review. <i>Nanotechnology</i> , 2019 , 30, 352003	3.4	101
97	Physical model of threshold switching in NbO2 based memristors. <i>RSC Advances</i> , 2015 , 5, 102318-1023	23 .7	100
96	Impact of Scaling on the Performance of HfO2-Based Ferroelectric Field Effect Transistors. <i>IEEE Transactions on Electron Devices</i> , 2014 , 61, 3699-3706	2.9	96
95	Nonlinear Dynamics of a Locally-Active Memristor. <i>IEEE Transactions on Circuits and Systems I:</i> Regular Papers, 2015 , 62, 1165-1174	3.9	92
94	On the stabilization of ferroelectric negative capacitance in nanoscale devices. <i>Nanoscale</i> , 2018 , 10, 10	8 9 1 7 10	8 99
93	Ferroelectric FETs With 20-nm-Thick HfO2 Layer for Large Memory Window and High Performance. <i>IEEE Transactions on Electron Devices</i> , 2019 , 66, 3828-3833	2.9	71
92	Evidence of single domain switching in hafnium oxide based FeFETs: Enabler for multi-level FeFET memory cells 2015 ,		64

(2019-2018)

91	Accumulative Polarization Reversal in Nanoscale Ferroelectric Transistors. <i>ACS Applied Materials & Amp; Interfaces</i> , 2018 , 10, 23997-24002	9.5	58	
90	Next generation ferroelectric materials for semiconductor process integration and their applications. <i>Journal of Applied Physics</i> , 2021 , 129, 100901	2.5	57	
89	On the relationship between field cycling and imprint in ferroelectric Hf0.5Zr0.5O2. <i>Journal of Applied Physics</i> , 2018 , 123, 204101	2.5	55	
88	Bipolar electric-field enhanced trapping and detrapping of mobile donors in BiFeO3 memristors. <i>ACS Applied Materials & Discours in BiFeO3 memristors</i> .	9.5	52	
87	Doped Hafnium Oxide IAn Enabler for Ferroelectric Field Effect Transistors. <i>Advances in Science and Technology</i> , 2014 , 95, 136-145	0.1	51	
86	Ferroelectric negative capacitance domain dynamics. <i>Journal of Applied Physics</i> , 2018 , 123, 184101	2.5	50	
85	2016,		48	
84	Direct Correlation of Ferroelectric Properties and Memory Characteristics in Ferroelectric Tunnel Junctions. <i>IEEE Journal of the Electron Devices Society</i> , 2019 , 7, 1175-1181	2.3	46	
83	Random Number Generation Based on Ferroelectric Switching. <i>IEEE Electron Device Letters</i> , 2018 , 39, 135-138	4.4	43	
82	Comparative Study of Reliability of Ferroelectric and Anti-Ferroelectric Memories. <i>IEEE Transactions on Device and Materials Reliability</i> , 2018 , 18, 154-162	1.6	42	
81	Reconfigurable NAND/NOR logic gates in 28 nm HKMG and 22 nm FD-SOI FeFET technology 2017 ,		39	
80	Hafnia-Based Double-Layer Ferroelectric Tunnel Junctions as Artificial Synapses for Neuromorphic Computing. <i>ACS Applied Electronic Materials</i> , 2020 , 2, 4023-4033	4	38	
79	Recovery of Cycling Endurance Failure in Ferroelectric FETs by Self-Heating. <i>IEEE Electron Device Letters</i> , 2019 , 40, 216-219	4.4	37	
78	Local ion irradiation-induced resistive threshold and memory switching in Nb2O5/NbO(x) films. <i>ACS Applied Materials & Discours (Materials & Discours)</i> 17474-80	9.5	36	
77	Filamentary resistive switching in amorphous and polycrystalline Nb2O5 thin films. <i>Solid-State Electronics</i> , 2012 , 72, 73-77	1.7	35	
76	Interplay between ferroelectric and resistive switching in doped crystalline HfO2. <i>Journal of Applied Physics</i> , 2018 , 123, 134102	2.5	33	
75	Memory technology-a primer for material scientists. <i>Reports on Progress in Physics</i> , 2020 , 83, 086501	14.4	32	
74	Negative Capacitance for Electrostatic Supercapacitors. <i>Advanced Energy Materials</i> , 2019 , 9, 1901154	21.8	31	

73	Built-In Bias Generation in Anti-Ferroelectric Stacks: Methods and Device Applications. <i>IEEE Journal of the Electron Devices Society</i> , 2018 , 6, 1019-1025	2.3	29
72	Ferroelectric field-effect transistors based on HfO: a review. <i>Nanotechnology</i> , 2021 , 32,	3.4	29
71	On Local Activity and Edge of Chaos in a NaMLab Memristor. Frontiers in Neuroscience, 2021 , 15, 651452	2 5.1	28
70	FeFET: A versatile CMOS compatible device with game-changing potential 2020,		26
69	Origin of the endurance degradation in the novel HfO2-based 1T ferroelectric non-volatile memories 2014 ,		24
68	The influence of crystallinity on the resistive switching behavior of TiO2. <i>Microelectronic Engineering</i> , 2011 , 88, 1148-1151	2.5	24
67	2022 roadmap on neuromorphic computing and engineering. <i>Neuromorphic Computing and Engineering</i> ,		24
66	Impact of Read Operation on the Performance of HfO2-Based Ferroelectric FETs. <i>IEEE Electron Device Letters</i> , 2020 , 41, 1420-1423	4.4	24
65	2019,		24
64	Progress and future prospects of negative capacitance electronics: A materials perspective. <i>APL Materials</i> , 2021 , 9, 020902	5.7	24
63	Pattern Formation With Locally Active S-Type NbOx Memristors. <i>IEEE Transactions on Circuits and Systems I: Regular Papers</i> , 2019 , 66, 2627-2638	3.9	22
62	Interplay Between Switching and Retention in HfO2-Based Ferroelectric FETs. <i>IEEE Transactions on Electron Devices</i> , 2020 , 67, 3466-3471	2.9	22
61	Demonstration of High-speed Hysteresis-free Negative Capacitance in Ferroelectric Hf0.5Zr0.5O2 2018 ,		22
60	Ferroelectric Tunnel Junctions based on Ferroelectric-Dielectric Hf0.5Zr0.5.O2/A12O3Capacitor Stacks 2018 ,		22
59	Impact of charge trapping on the ferroelectric switching behavior of doped HfO2. <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2016 , 213, 270-273	1.6	21
58	Compact FeFET Circuit Building Blocks for Fast and Efficient Nonvolatile Logic-in-Memory. <i>IEEE Journal of the Electron Devices Society</i> , 2020 , 8, 748-756	2.3	19
57	Correlation between the macroscopic ferroelectric material properties of Si:HfO2 and the statistics of 28 nm FeFET memory arrays. <i>Ferroelectrics</i> , 2016 , 497, 42-51	0.6	19
56	Reconfigurable frequency multiplication with a ferroelectric transistor. <i>Nature Electronics</i> , 2020 , 3, 391	-3987.4	18

55	2019,		17
54	Investigation of Accumulative Switching in Ferroelectric FETs: Enabling Universal Modeling of the Switching Behavior. <i>IEEE Transactions on Electron Devices</i> , 2020 , 67, 5804-5809	2.9	17
53	A Silicon Nanowire Ferroelectric Field-Effect Transistor. <i>Advanced Electronic Materials</i> , 2020 , 6, 1901244	6.4	16
52	Ferroelectric Hf1-xZrxO2 memories: device reliability and depolarization fields 2019 ,		15
51	Demonstration of versatile nonvolatile logic gates in 28nm HKMG FeFET technology 2018,		13
50	Demonstration of a p-Type Ferroelectric FET With Immediate Read-After-Write Capability. <i>IEEE Electron Device Letters</i> , 2021 , 42, 1774-1777	4.4	13
49	Uniting The Trinity of Ferroelectric HfO2 Memory Devices in a Single Memory Cell 2019 ,		12
48	Embedding hafnium oxide based FeFETs in the memory landscape 2018,		11
47	Performance investigation and optimization of Si:HfO2 FeFETs on a 28 nm bulk technology 2013,		11
46	Perspective on ferroelectric, hafnium oxide based transistors for digital beyond von-Neumann computing. <i>Applied Physics Letters</i> , 2021 , 118, 050501	3.4	11
45	Multiple slopes in the negative differential resistance region of NbO x -based threshold switches. Journal Physics D: Applied Physics, 2019 , 52, 325104	3	10
44	Room temperature fabricated NbOx/Nb2O5 memory switching device with threshold switching effect 2013 ,		10
43	Intrinsic Nature of Negative Capacitance in Multidomain Hf0.5Zr0.5O2-Based Ferroelectric/Dielectric Heterostructures. <i>Advanced Functional Materials</i> ,2108494	15.6	9
42	Impact of area scaling on the ferroelectric properties of back-end of line compatible Hf0.5Zr0.5O2 and Si:HfO2-based MFM capacitors. <i>Applied Physics Letters</i> , 2021 , 118, 062904	3.4	9
41	Ferroelectric transistors with asymmetric double gate for memory window exceeding 12 V and disturb-free read. <i>Nanoscale</i> , 2021 , 13, 16258-16266	7.7	9
40	Built-in bias fields for retention stabilisation in hafnia-based ferroelectric tunnel junctions. <i>Electronics Letters</i> , 2020 , 56, 1108-1110	1.1	8
39	Improved Vertex Coloring With NbOx Memristor-Based Oscillatory Networks. <i>IEEE Transactions on Circuits and Systems I: Regular Papers</i> , 2021 , 1-14	3.9	8
38	Integration of niobium oxide-based resistive switching cells with different select properties into nanostructured cross-bar arrays. <i>Semiconductor Science and Technology</i> , 2015 , 30, 115014	1.8	7

37	A 2TnC ferroelectric memory gain cell suitable for compute-in-memory and neuromorphic application 2019 ,		6
36	Ultra-dense co-integration of FeFETs and CMOS logic enabling very-fine grained Logic-in-Memory 2019 ,		6
35	Inherent Charge-Sharing-Free Dynamic Logic Gates Employing Transistors With Multiple Independent Inputs. <i>IEEE Journal of the Electron Devices Society</i> , 2020 , 8, 740-747	2.3	6
34	Reliability Comparison of ZrO2-Based DRAM High-k Dielectrics Under DC and AC Stress. <i>IEEE Transactions on Device and Materials Reliability</i> , 2017 , 17, 324-330	1.6	5
33	Unfolding the Threshold Switching Behavior of a Memristor. <i>Communications in Computer and Information Science</i> , 2014 , 156-164	0.3	5
32	Graph Coloring via Locally-Active Memristor Oscillatory Networks. <i>Journal of Low Power Electronics and Applications</i> , 2022 , 12, 22	1.7	5
31	Improvement of NbO x -based threshold switching devices by implementing multilayer stacks. <i>Semiconductor Science and Technology</i> , 2019 , 34, 075005	1.8	4
30	Ferroelectric-based synapses and neurons for neuromorphic computing. <i>Neuromorphic Computing and Engineering</i> , 2022 , 2, 012002		4
29	Analysis of Vth variability in NbOx-based threshold switches 2016 ,		4
28	Antiferroelectric negative capacitance from a structural phase transition in zirconia <i>Nature Communications</i> , 2022 , 13, 1228	17.4	4
27	Negative Capacitance in HfO2- and ZrO2-Based Ferroelectrics 2019 , 473-493		3
²⁷	Negative Capacitance in HfO2- and ZrO2-Based Ferroelectrics 2019 , 473-493 Switching and Charge Trapping in HfO2-based Ferroelectric FETs: An Overview and Potential Applications 2020 ,		3
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26	Switching and Charge Trapping in HfO2-based Ferroelectric FETs: An Overview and Potential Applications 2020 ,		3
26 25	Switching and Charge Trapping in HfO2-based Ferroelectric FETs: An Overview and Potential Applications 2020, Influence of nitrogen trap states on the electronic properties of high-k metal gate transistors 2014, Polarization switching and interface charges in BEOL compatible Ferroelectric Tunnel Junctions		3
26 25 24	Switching and Charge Trapping in HfO2-based Ferroelectric FETs: An Overview and Potential Applications 2020, Influence of nitrogen trap states on the electronic properties of high-k metal gate transistors 2014, Polarization switching and interface charges in BEOL compatible Ferroelectric Tunnel Junctions 2021,		3 3
26 25 24 23	Switching and Charge Trapping in HfO2-based Ferroelectric FETs: An Overview and Potential Applications 2020, Influence of nitrogen trap states on the electronic properties of high-k metal gate transistors 2014, Polarization switching and interface charges in BEOL compatible Ferroelectric Tunnel Junctions 2021, Reliability aspects of ferroelectric hafnium oxide for application in non-volatile memories 2021,		3 3 3

19	Atomic layer etching of ferroelectric hafnium zirconium oxide thin films enables giant tunneling electroresistance. <i>Applied Physics Letters</i> , 2022 , 120, 122901	3.4	3
18	Thickness Scaling of AFE-RAM ZrO2 Capacitors with High Cycling Endurance and Low Process Temperature 2020 ,		2
17	Hafnium oxide based ferroelectric devices for memories and beyond 2018,		2
16	A multi-pulse wakeup scheme for on-chip operation of devices based on ferroelectric doped HfO2 thin films. <i>Applied Physics Letters</i> , 2022 , 120, 022901	3.4	2
15	C-AND: Mixed Writing Scheme for Disturb Reduction in 1T Ferroelectric FET Memory. <i>IEEE Transactions on Circuits and Systems I: Regular Papers</i> , 2022 , 1-11	3.9	2
14	High-Performance Operation and Solder Reflow Compatibility in BEOL-Integrated 16-Kb HfO Si-Based 1T-1C FeRAM Arrays. <i>IEEE Transactions on Electron Devices</i> , 2022 , 1-7	2.9	2
13	Materials for DRAM Memory Cell Applications. <i>Materials and Energy</i> , 2016 , 369-401		2
12	Negative capacitance devices: sensitivity analyses of the developed TCAD ferroelectric model for HZO. <i>Journal of Instrumentation</i> , 2022 , 17, C01048	1	1
11	Nonvolatile Field-Effect Transistors Using Ferroelectric-Doped HfO2 Films. <i>Topics in Applied Physics</i> , 2020 , 79-96	0.5	1
10	FeFETs for Neuromorphic Systems. <i>Topics in Applied Physics</i> , 2020 , 399-411	0.5	1
9	Switching in Nanoscale Hafnium Oxide-Based Ferroelectric Transistors. <i>Topics in Applied Physics</i> , 2020 , 97-108	0.5	1
8	Flexible Memory, Bit-Passing and Mixed Logic/Memory Operation of two Intercoupled FeFET Arrays 2020 ,		1
7	Frequency Mixing with HfO-Based Ferroelectric Transistors. <i>ACS Applied Materials & Amp; Interfaces</i> , 2020 , 12, 44919-44925	9.5	1
6	FeFET based Logic-in-Memory: an overview 2021 ,		1
5	Dynamic modeling of hysteresis-free negative capacitance in ferroelectric/dielectric stacks under fast pulsed voltage operation 2019 ,		1
4	TCAD numerical modeling of negative capacitance ferroelectric devices for radiation detection applications. <i>Solid-State Electronics</i> , 2022 , 194, 108341	1.7	1
3	A FeFET-based hybrid memory accessible by content and by address. <i>IEEE Journal on Exploratory Solid-State Computational Devices and Circuits</i> , 2022 , 1-1	2.4	О
2	Versatile experimental setup for FTJ characterization. <i>Solid-State Electronics</i> , 2022 , 194, 108364	1.7	Ο

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